

## Chemisorption of CH<sub>3</sub>OH on Si(111)-7x7: Density-functional theory calculations

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CH<sub>3</sub>OH is known to dissociate into CH<sub>3</sub>O + H on the Si(111)-(7x7) surface. Despite many studies, however, the reactive site on the Si(111)-(7x7) surface towards CH<sub>3</sub>OH molecules has not yet been identified. We investigate the chemisorption mechanism of CH<sub>3</sub>OH on Si(111)-(7x7) using density-functional theory (DFT) calculations. The adatom site is found to be reactive towards CH<sub>3</sub>OH, and the restatom site repulsive towards CH<sub>3</sub>OH. CH<sub>3</sub>OH molecules adsorbed on the adatom dissociate into CH<sub>3</sub>O + H without a barrier, thus forming surface species CH<sub>3</sub>O-Si (adatom) and H-Si (restatom). The present reaction picture of the higher adatom reactivity is consistent with a dissociation geometry reported by a scanning tunneling microscopy study<sup>(1)</sup>, but differs from the prediction of photoemission spectroscopy studies<sup>(2,3)</sup> and a DFT study<sup>(4)</sup> that the restatom is more reactive than the adatom towards CH<sub>3</sub>OH. The origin of the discrepancy between the present and the previous studies will be discussed.

### References

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